

Plasma Chemistry and Kinetics in Low Pressure Oxygen Discharges: The significance of metastable states

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Outline

- The oxygen discharge is of significance in various materials processing applications including
 - etching of polymer films
 - ashing of photoresist
 - oxidation
- The oxygen chemistry is complicated due to the presence of metastable atomic and molecular species
- It is in particular the two low lying metastable molecular states designated by $a^1\Delta_g$ and $b^1\Sigma_g^+$, which are located 0.98 and 1.627 eV above the ground state, respectively
- It is well established that collisions with these metastable states have in many cases larger cross sections and thus higher reaction rates than corresponding collisions with the ground state molecule
- The discharge electronegativity is dictated by these metastable states



- A. Global (volume averaged) chemistry models
 - A1 The oxygen discharge
 - chlorine dilution
- B. 1D particle-in-cell/Monte Carlo collision simulation
 - B.1 Capacitively Coupled Oxygen Discharge at 13.56 MHz
 - pressure dependence
 - driving frequency dependence
 - surface quenching of $O_2(a^1\Delta_g)$
 - the effect of $\gamma_{\text{see}}(\mathcal{E})$
- C. Summary

A. Global (volume averaged) chemistry models



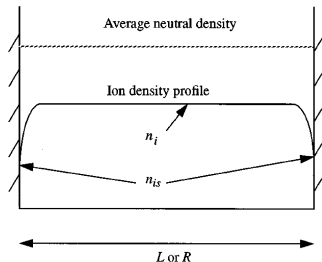
Global (volume averaged) chemistry models

- The main idea of a global model is to generate a model that encompasses a large number of reactions in order to model a processing plasma with a limited computing power by neglecting the complexity which arises when spatial variations are considered
- Thus the model does not describe spatial distribution but captures scalings of plasma parameters with control parameters
- The model allows us to investigate various phenomena, such as the effects of excited species, negative ions and particular reactions on the overall discharge

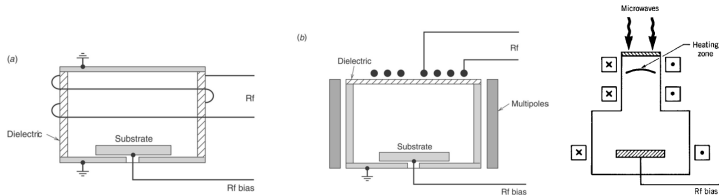


Global (volume averaged) chemistry models

- The densities of all species are assumed to be volume averaged
- For an electropositive discharge the positive-ion densities are assumed to have a uniform profile throughout the discharge except near the wall, where the density is assumed to drop sharply to a sheath-edge density n_{is}
- The electron energy distribution function (EEDF) is assumed (usually Maxwellian)
- The ion and neutral temperature have to be assumed



Global (volume averaged) chemistry models



From Lieberman and Lichtenberg (2005)

- This kind of model can be applied to explore the plasma chemistry of low pressure high density discharges such as
 - inductively coupled discharge
 - electron cyclotron resonance (ECR) discharge

A.1 Global (volume averaged) chemistry models – oxygen



The global (volume averaged) model

- A steady state global (volume averaged) model was developed for the oxygen discharge
- The following species are included
 - electrons
 - the ground state oxygen molecule $O_2(X^3\Sigma_g^-, v = 0)$,
 - The metastable oxygen molecules $O_2(a^1\Delta_g)$, $O_2(b^1\Sigma_g^+)$ and the metastable Herzberg states $O_2(A^3\Sigma_u^+, A'^3\Delta_u, c^1\Sigma_u^-)$
 - the ground state oxygen atom $O(^3P)$
 - the metastable oxygen atom $O(^1D)$
 - the negative oxygen ions O^- and O_2^-
 - the positive oxygen ions O^+ and O_2^+
 - Ozone O_3 and its ions O_3^+ and O_3^-
- The content of the chamber is assumed to be nearly spatially uniform and the power is deposited uniformly into the plasma bulk



The global (volume averaged) model

- The particle balance equation for a species X is given as

$$\frac{dn^{(X)}}{dt} = 0 = \sum_i R_{\text{Generation},i}^{(X)} - \sum_i R_{\text{Loss},i}^{(X)}$$

where $R_{\text{Generation},i}^{(X)}$ and $R_{\text{Loss},i}^{(X)}$, respectively, are the reaction rates of the various generation and loss processes of the species X

- Since the discharge is assumed to be quasi-neutral,

$$n_e = \sum_i Z_i n_i$$

where Z_i is the charge of ion i , an equation describing the particle balance of free electrons is not required



The global (volume averaged) model

- To investigate the creation and destruction of species we compare the reaction rates
- The reaction rate R for a given reaction is calculated as the product of the reactants, densities and the rate coefficient k of the reaction,

$$R = k \times \prod_i n_{r,i} \quad [\text{m}^{-3}\text{s}^{-1}]$$

where $n_{r,i}$ is the density of the i -th reactant.

- The rate coefficient for electron impact reactions is

$$k = \langle v\sigma \rangle = 4\pi \int_0^\infty f(v)\sigma(v)v^3 dv$$



The global (volume averaged) model

- The power balance equation, equates the absorbed power P_{abs} to power losses due to elastic and inelastic collisions and losses due to charged particle flow to the walls is given as

$$\frac{1}{V} \left[P_{\text{abs}} - eVn_e \sum_{\alpha} n^{(\alpha)} \mathcal{E}_c^{(\alpha)} k_{iz}^{(\alpha)} - eu_{B0} n_i A_{\text{eff}} (\mathcal{E}_i + \mathcal{E}_e) \right] = 0$$

where

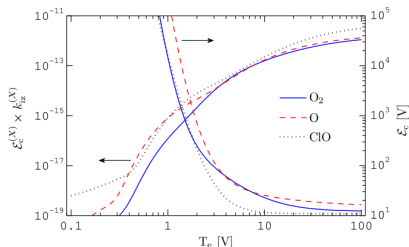
- V is the volume of the discharge chamber
- $A_{\text{eff}} = 2\pi(R^2 h_L + RLh_R)$ is the effective area for ion loss
- $u_{B0} = \left[\frac{eT_e}{m_i} \right]^{1/2}$ is the Bohm velocity



The global (volume averaged) model

- $\mathcal{E}_i = V_p + V_s$ is the mean kinetic energy lost per ion lost
- $\mathcal{E}_e = 2T_e$ is the mean kinetic energy lost per electron lost
- $\mathcal{E}_c^{(\alpha)}$ is the collisional energy loss per electron-ion pair created

$$\mathcal{E}_c^{(X)} = \mathcal{E}_{iz}^{(X)} + \sum_i \mathcal{E}_{ex,i}^{(X)} \frac{k_{ex,i}^{(X)}}{k_{iz}^{(X)}} + \frac{k_{el}^{(X)}}{k_{iz}^{(X)}} \frac{3m_e}{m^{(X)}} T_e$$



The global (volume averaged) model

- For the edge-to-center positive ion density ratio we use

$$h_{\ell} \simeq \left[\left(\frac{0.86}{(3 + \eta L/2\lambda_i)^{1/2}} \frac{1}{1 + \alpha_0} \right)^2 + h_c^2 \right]^{1/2}$$

$$h_R \simeq \left[\left(\frac{0.8}{(4 + \eta R/\lambda_i)^{1/2}} \frac{1}{1 + \alpha_0} \right)^2 + h_c^2 \right]^{1/2}$$

where $\alpha_0 \approx (3/2)\alpha$ is the central electronegativity,
 $\eta = 2T_+/(T_+ + T_-)$ and

$$h_c \simeq \left[\gamma_-^{1/2} + \gamma_+^{1/2} [n_*^{1/2} n_+ / n_-^{3/2}] \right]^{-1} \quad \text{and} \quad n_* = \frac{15}{56} \frac{\eta^2}{k_{\text{rec}} \lambda_i} v_i$$

is based on a one-region flat topped electronegative profile

$$\gamma_- = T_e/T_- \quad \text{and} \quad \gamma_+ = T_e/T_+$$



The global (volume averaged) model

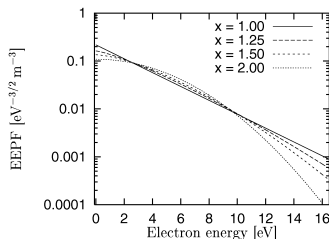
- The electron energy distribution function (EEDF) is usually assumed to be Maxwellian
- We can also assume a general electron energy distribution

$$g_e(\mathcal{E}) = c_1 \mathcal{E}^{1/2} \exp(-c_2 \mathcal{E}^x)$$

$$c_1 = \frac{1}{\langle \mathcal{E} \rangle^{3/2}} \frac{[\Gamma(\xi_2)]^{3/2}}{[\Gamma(\xi_1)]^{5/2}} \quad \text{and} \quad c_2 = \frac{1}{\langle \mathcal{E} \rangle^x} \frac{[\Gamma(\xi_2)]}{[\Gamma(\xi_1)]^x}$$

where $\xi_1 = 3/2x$ and $\xi_2 = 5/2x$

- Here $x = 1$ and $x = 2$ correspond to Maxwellian and Druyvesteyn electron energy distributions, respectively



$$g_p(\mathcal{E}) = \frac{g_e(\mathcal{E})}{\mathcal{E}^{1/2}}$$

The global (volume averaged) model

- The diffusional losses of the neutral oxygen atoms (ground state and metastable) to the reactor walls are given by

$$k_{O,wall} = \left[\frac{\Lambda_O^2}{D_O} + \frac{2V(2 - \gamma_{rec})}{Av_O\gamma_{rec}} \right]^{-1} s^{-1}$$

- D_O is the diffusion coefficient for oxygen atoms
- $v_O = (8eT_g/\pi m_O)^{1/2}$ is the mean O velocity
- γ_{rec} is the wall recombination coefficient for neutral oxygen atoms on the wall surface
- Λ_O is the effective diffusion length of neutral oxygen atoms

$$\Lambda_O = \left[\left(\frac{\pi}{L} \right)^2 + \left(\frac{2.405}{R} \right)^2 \right]^{-1/2}$$

- The wall recombination coefficient γ_{rec} is one of the most important parameter in oxygen discharge modelling



A.2.1 Model parameters



Surface recombination

- The wall recombination probability, γ_{rec} , is a very important quantity in all low pressure molecular discharges
- The pressure dependence on the wall recombination coefficient was achieved by fitting all the available data for stainless steel surfaces
- The same wall recombination coefficient was used for $\text{O}(^1\text{D})$ as no data is available

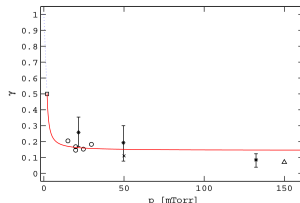


Figure 1. The recombination coefficient of oxygen atoms at the chamber walls for stainless steel as a function of pressure. The measured data is taken from, o Singh *et al* [47], x Matsushita *et al* [90], Δ Mozetić and Zalar [91], \square Booth and Sadeghi [44] and * Gomez *et al* [46]. The solid line shows a fit to the measured data and the dotted line is a linear extrapolation from $\gamma = 0.5$ at 2 mTorr to $\gamma = 1.0$ at vacuum.

The wall recombination coefficient for oxygen atoms on stainless steel surfaces depends on pressure through

$$\gamma_{\text{rec}} = 0.1438 \exp(2.5069/p) \quad p > 2 \text{ mTorr}$$

$$\gamma_{\text{rec}} = -0.25p + 1 \quad p < 2 \text{ mTorr}$$

A.2.3 Particle densities

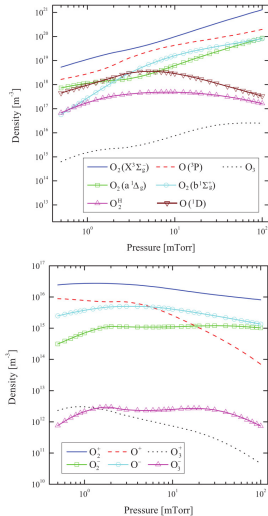


Particle densities – neutrals

- The dominant species is the oxygen molecule in the ground state $O_2(X^3\Sigma_g)$ followed by the oxygen atom in the ground state $O(^3P)$
- The singlet metastable states $O_2(a^1\Delta_g)$ and $O_2(b^1\Sigma_g^+)$ and the metastable atom $O(^1D)$ are also present in the plasma in significant amounts
- a cylindrical stainless steel chamber

radius $R = 15$ cm and length $L = 30$ cm $P_{abs} = 500$ W

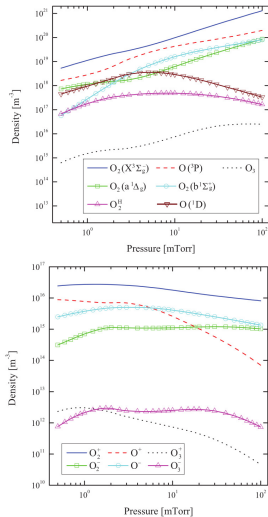
Toneli et al., *J. Phys. D*, **48** (2015) 325202



Particle densities – neutrals

- The $O_2(b^1\Sigma_g^+)$ density overcomes the $O_2(a^1\Delta_g)$ density in the pressure range from 2.5 to 80 mTorr
- The O_2^+ ions are in majority among the positive ions
- The O^+ density has a sharp decrease for pressures above 4 mTorr
- The ratio $[O^-]/[O_2^-]$ is 5.3 at 1 mTorr, and 1.3 at 100 mTorr
- a cylindrical stainless steel chamber

radius $R = 15$ cm and length $L = 30$ cm $P_{abs} = 500$ W



Particle densities – negative ions

- O^- -ions are the dominating negative ions at low pressure
- The density of O_2^- and O_3^- is much smaller
- The importance of O_2^- -ions increases with increasing pressure
- Measurements of the negative ion densities in a capacitive rf discharge in the pressure range 70 – 350 mTorr indicate that O_2^- -ions are less than 2 % of all negative ions

Katsch et al., *PSST*, **9** (2000) 323

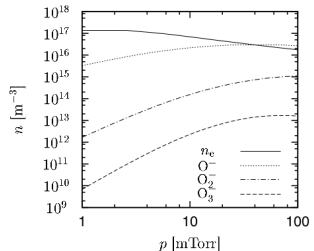


Figure 6. The densities of electrons n_e and negative oxygen ions, O^- , O_2^- , and O_3^- , versus discharge pressure at 500 W and a flow rate of 50 sccm for a cylindrical stainless steel chamber with $L = 7.6$ cm and $R = 15.2$ cm.

Gudmundsson et al., *J. Phys. D*, **34** (2001) 1100



Particle densities – negative ions

- The electronegativity

$$\alpha = \frac{n_- + n_{2-} + n_{3-}}{n_e}$$

versus pressure

- The low pressure high density oxygen discharge is weakly electronegative
- The electronegativity decreases with increasing absorbed power

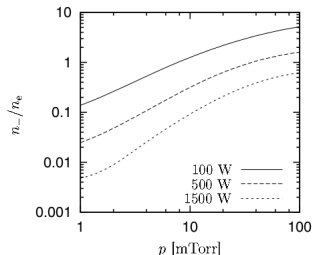
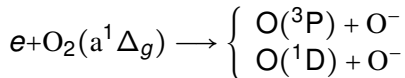


Figure 7. The electronegativity $n_-/(n_- + n_{2-} + n_{3-})$ at 100, 500 and 1500 W versus discharge pressure. We assume a flow rate of 50 sccm and a cylindrical stainless steel chamber with $L = 7.6$ cm and $R = 15.2$ cm.

Creation of the negative ion O^-

- Roughly half of the negative O^- -ions in a pure oxygen discharge are created through dissociative attachment from the metastable oxygen molecule $O_2(a^1\Delta_g)$:



at 10 mTorr and 500 W applied power

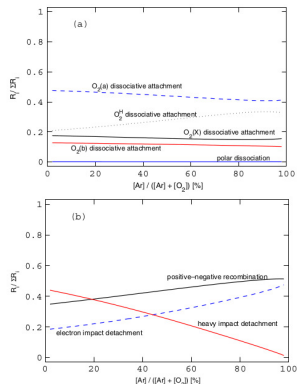


Figure 10. The reaction rates for (a) the creation of the O^- ion and (b) the loss of the O^- ion versus fractional argon flow rate $[Ar]/([Ar] + [O_2])$. The applied power is 500 W, the gas flow rate is 50 sccm and pressure is of 10 mTorr. The chamber is assumed to be made of stainless steel, cylindrical with $R = 10$ cm and $L = 10$ cm.



Creation of the negative ion O^-

- Roughly 20% are created through dissociative attachment from $O_2(A^3\Sigma_u^+, A^3\Delta_u, c^1\Sigma_u^-)$
- Dissociative attachment of the oxygen molecule is almost the sole source of O^- in the discharge and the metastable oxygen molecules play a major role in the creation of negative ions

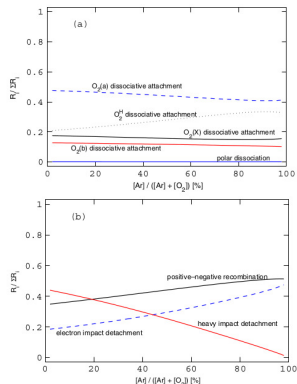
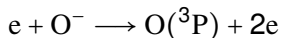


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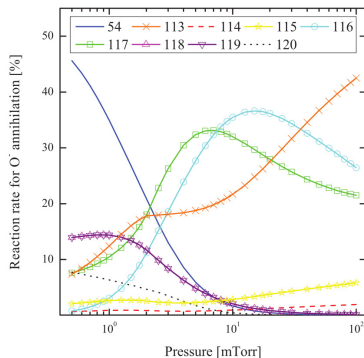
Destruction of the negative ion O^-

- At low pressure that the electron impact detachment (54),



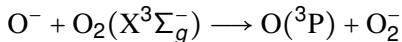
is the main contributor to the loss of O^-

- Ion-ion mutual neutralization is also important (118, 119, 120) at low pressure
- As pressure increases, the contributions of these reactions become negligible

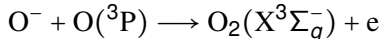


Destruction of the negative ion O^-

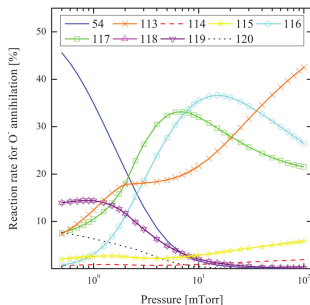
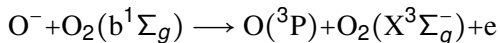
- As the pressure increases charge exchange (113)



and detachment by collision with $O(^3P)$ (117)



have increased contribution as well as detachment by collision with $O_2(b^1\Sigma_g)$ (reaction 116)

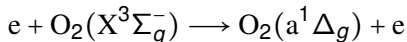


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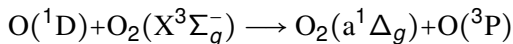
Creation of metastable $O_2(a^1\Delta_g)$ molecules

■ Electron impact excitation (17)

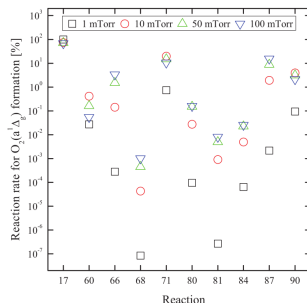


has 100 % contribution at 1 mTorr
and 68.2 % at 100 mTorr

■ The role of quenching of the metastable atom $O(^1D)$ to create the metastable oxygen molecule (71)



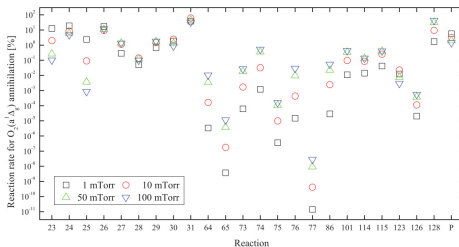
reaches a maximum value, 20.1 %
contribution at 12.5 mTorr, and 10.5
% at 100 mTorr



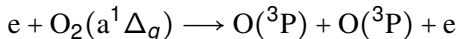
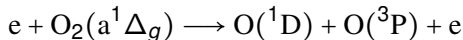
Toneli et al., *J. Phys. D*, **48** (2015) 325202



Destruction of metastable $O_2(a^1\Delta_g)$ molecules



■ Electron impact dissociation (31,24)

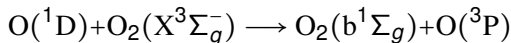


are the most important channels for destruction of the metastable $O_2(a^1\Delta_g)$ molecules, 57.2 % contribution at 1 mTorr and 38.1 % at 100 mTorr



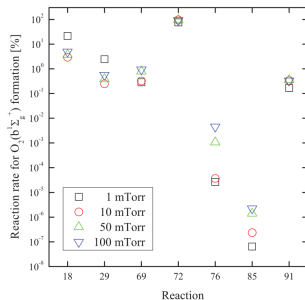
Creation of metastable $O_2(b^1\Sigma_g)$ molecules

- The most important contributor to the formation of the metastable oxygen molecule $O_2(b^1\Sigma_g)$ is reaction 72



which has 75.7 % contribution at 1 mTorr and 93.2 % at 100 mTorr

- This reaction has been suggested in the past to be a major contributor to the formation of $b^1\Sigma_g^+$ state in the atmosphere

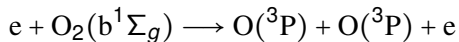
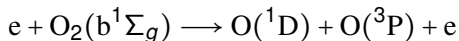


Toneli et al., *J. Phys. D*, **48** (2015) 325202

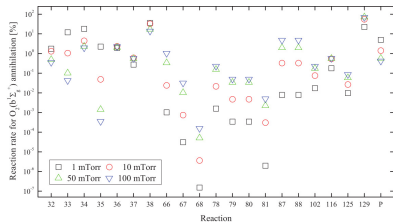
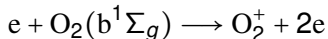


Destruction of metastable $O_2(b^1\Sigma_g)$ molecules

- Wall quenching is an important loss process for $O_2(b^1\Sigma_g)$
- Electron impact dissociation (38,34)



are the most important channels for destruction along with electron impact ionization (33)



Toneli et al., *J. Phys. D*, **48** (2015) 325202

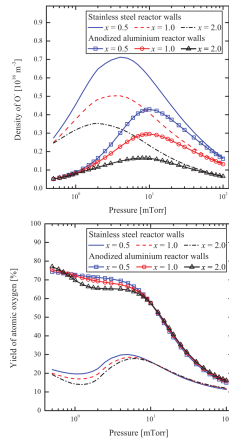


A.2.4 Influence of chamber wall and EEDF



Influence of chamber wall and EEDF

- The parameter x defines the shape of the electron energy distribution
 - $x = 0.5$ is concave or bi-Maxwellian
 - $x = 1$ is a Maxwellian distribution
 - $x = 2$ is Druyvesteyn distribution
- For anodized aluminium reactor walls, the recombination coefficient for oxygen atoms at the walls is assumed to be a constant $\gamma_O = 0.06$ based on the measurements of Guha et al. (2008)
- The chamber wall has a significant influence on the dissociation fraction

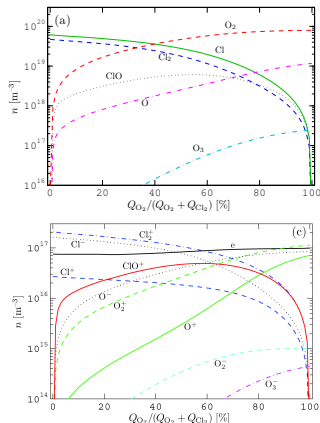


A.2.5 Chlorine dilution



Chlorine dilution – Particle densities

- The chlorine-oxygen molecule ClO and its ion ClO⁺ peak when Cl₂ and O₂ flowrates are roughly equal
- The O₂(a¹Δ_g) density is about 9 – 10 % of the total O₂ density
- The electron density increases about 30 % between pure chlorine and pure oxygen discharge



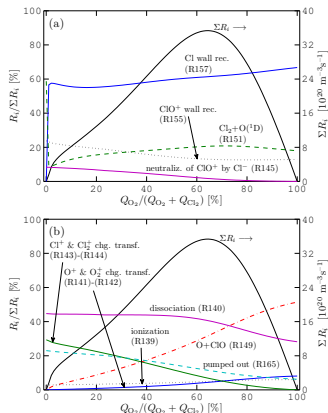
Thorsteinsson and Gudmundsson, *Plasma Sources Sci. Technol.*, **19** 055008 (2010)

A cylindrical stainless steel chamber
 $L = 10$ cm and $R = 10$ cm
 $p = 10$ mTorr and $P_{\text{abs}} = 500$ W



Oxygen dilution – Particle densities

- The total rate for creation and loss of ClO molecules is at maximum when the oxygen content is 65%
- Wall recombination of Cl molecules, is the dominating pathway for creation of ClO molecules
- The bulk processes and recombination of ClO^+ ions at the wall account for roughly 33–43% of the total rate for ClO creation, combined

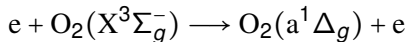


A.3 Summary

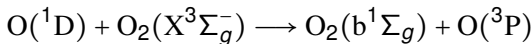


Summary

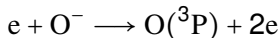
- A global model of O_2 , and Cl_2/O_2 discharges has been applied to explore the creation and destruction of the singlet metastable molecules $O_2(a^1\Delta_g)$, $O_2(b^1\Sigma_g^+)$
- The singlet delta state $O_2(a^1\Delta_g)$ is created mainly by electron impact excitation



- The singlet delta state $O_2(b^1\Sigma_g^+)$ is created mainly by



- At low pressure that the electron impact detachment



is the main contributor to the loss of O^-

- The ClO molecule is mainly created by recombination at the discharge wall

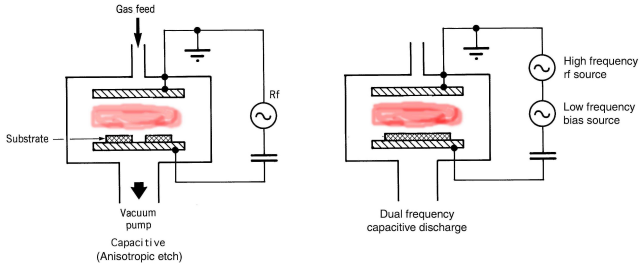


B. 1D particle-in-cell/Monte Carlo collision simulation



- B.1 The 1D particle-in-cell/Monte Carlo collision simulation
 - The oxygen discharge
 - Capacitively Coupled Oxygen Discharge at 13.56 MHz
 - pressure dependence
 - driving frequency dependence
 - surface quenching of $O_2(a^1\Delta_g)$
 - the effect of $\gamma_{\text{see}}(\mathcal{E})$
 - Summary

Introduction



- One of the most widely used types of low-pressure discharges is sustained by radio-frequency (rf) currents and voltages, introduced through a capacitive sheaths
- The currents in the main body of the plasma lead to Ohmic heating, while the voltage across the sheath leads to stochastic sheath heating

The 1D particle-in-cell/Monte Carlo collision simulation



The oopd1 1d-3v PIC/MCC code

- In particle-in-cell simulation the plasma is represented as a collection of macroparticles
- Each macroparticle is a charged “cloud” representing many real charged particles
- Each macroparticle has the same charge-to-mass ratio (q/m) as the real charged particle
- Equations of motion are solved for each macroparticle
- The electric and magnetic fields are calculated self-consistently using charge densities and currents produced by the macroparticles



The oopd1 1d-3v PIC/MCC code

- We use the `oopd1` (objective oriented plasma device for one dimension) code to simulate the discharge
- The `oopd1` code was originally developed at the Plasma Theory and Simulation Group at UC Berkeley
- It has 1 dimension in space and 3 velocity components for particles (1d-3v)
- The `oopd1` code is supposed to replace the widely used `xpdx1` series (`xpdp1`, `xpdc1` and `xpds1`)
- It is developed to simulate various types of plasmas, including processing discharges, accelerators and beams
 - Modular structure
 - Includes relativistic kinematics
 - Particles can have different weights

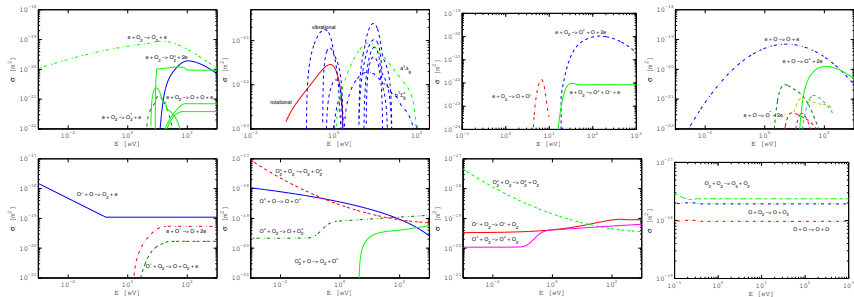
B.2. The oxygen discharge



The oxygen discharge

- We consider a discharge that consists of:
 - electrons
 - the ground state oxygen molecule $O_2(X^3\Sigma_g^-)$
 - the metastable oxygen molecule $O_2(a^1\Delta_g)$
 - the metastable oxygen molecule $O_2(b^1\Sigma_g)$
 - the ground state oxygen atom $O(^3P)$
 - the metastable oxygen atom $O(^1D)$
 - the negative oxygen ion O^-
 - the positive oxygen ions O^+ and O_2^+
- The discharge model includes energy dependent secondary electron emission yield
- We assume a parallel plate capacitively coupled oxygen discharge at with electrode separation of 4.5 cm
- We apply a global model¹ beforehand to calculate the partial pressure of the various neutrals

The oxygen discharge



- The reaction set for the oxygen is comprehensive and for this study includes 67 reactions

Gudmundsson et al., *Plasma Sources Sci. Technol.*, **22** 035011 (2013)

Gudmundsson and Lieberman, *Plasma Sources Sci. Technol.*, **24** 035016 (2015)

Hannesdottir and Gudmundsson, *Plasma Sources Sci. Technol.*, **25** 055002 (2016)

Capacitively Coupled Oxygen Discharge single frequency at 13.56 MHz

– pressure dependence –

including $\text{O}_2(\text{a}^1\Delta_g)$ with $\gamma_{\text{see}} = 0.0$



Oxygen CCP – pressure dependence

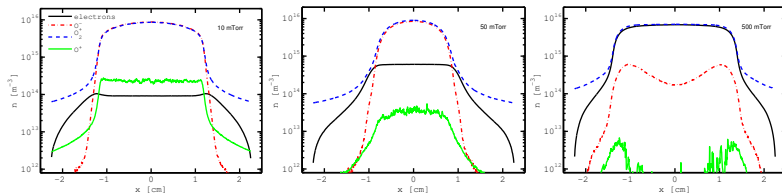
- We apply a voltage source with a single frequency

$$V(t) = V_{\text{rf}} \sin(2\pi ft)$$

- The electrodes are circular with a diameter of 14.36 cm
- The gap between the electrodes is 4.5 cm
- We set $V_{\text{rf}} = 222$ V and $f = 13.56$ MHz
- The neutrals (O_2 and O) are treated as background gas at $T_g = 300$ K with a Maxwellian distribution
- The dissociation fraction and the metastable fraction is found using a global model
- The pressure is varied from 10 – 500 mTorr

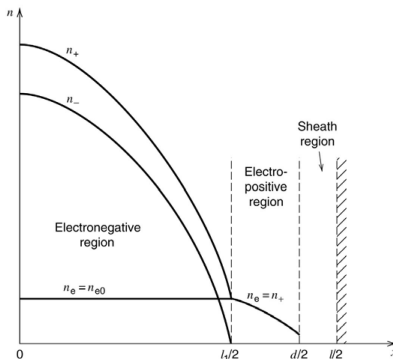


Oxygen CCP – pressure dependence



- For a parallel plate capacitively coupled oxygen discharge at 10, 50 and 500 mTorr with a gap separation of 4.5 cm by a 222 V voltage source at 13.56 MHz
 - O_2^+ -ion density profile
 - O^+ -ion density profile
 - O^- -ion density profile
 - electron density profile

Oxygen CCP – pressure dependence

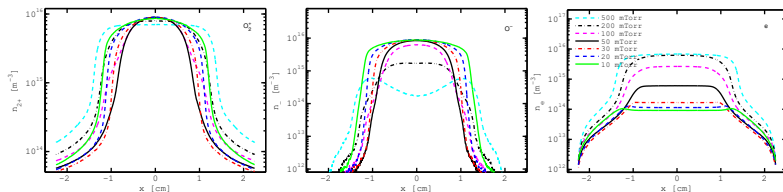


Lieberman and Lichtenberg (2005)

- In the electronegative discharge the plasma tends to stratify into an electronegative core and electropositive edge



Oxygen CCP – pressure dependence



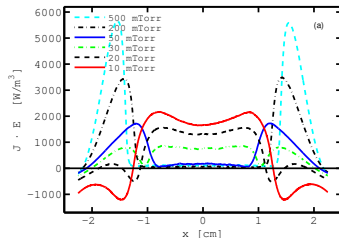
- The sheath width decreases as the pressure is decreased in the pressure range from 50 mTorr to 10 mTorr
- The sheath widths are largest at 50 mTorr
- As the pressure is increased from 50 mTorr up to 500 mTorr the sheath width decreases
- This agrees with what has been observed experimentally in the pressure range 40 – 375 mTorr

Mutsukura et al. (1990) JAP **68** 2657 and van Roosmalen et al. (1985) JAP **58** 653



Oxygen CCP – pressure dependence

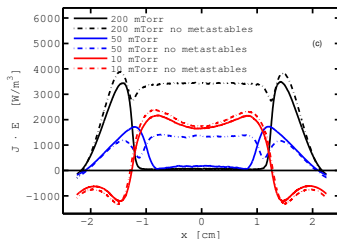
- The electron heating profile $\mathbf{J_e \cdot E}$
- In the pressure range 50 - 500 mTorr the electron heating occurs almost solely in the sheath region
- As the pressure is decreased the Ohmic heating contribution in the plasma bulk increases and sheath heating decreases



Gudmundsson and Ventéjou (2015) JAP **118** 153302

Oxygen CCP – pressure dependence

- At **10 mTorr** excluding the metastable states in the simulation has very small influence on the heating mechanism
- At **50 mTorr** the metastable states have a significant influence on the heating mechanism
- The role of the metastables is even more significant at **200 mTorr**

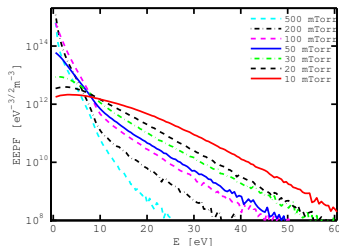


Gudmundsson and Ventéjou (2015) JAP **118** 153302

Gudmundsson and Lieberman (2015) PSST **24** 035016

Oxygen CCP – pressure dependence

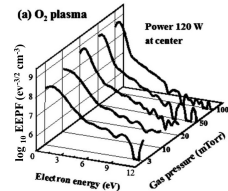
- At low pressure the EEPF curves outwards, the population of low energy electrons is relatively low
- As the pressure is increased the number of low energy electrons increases and the number of higher energy electrons (> 10 eV) decreases
- Thus the EEPF curves inwards or becomes bi-Maxwellian as the pressure is increased



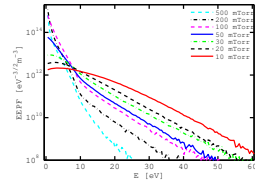
Gudmundsson and Ventéjou (2015) JAP **118** 153302

Oxygen CCP – pressure dependence

- Our results agree with the measurements of Lee et al. (2010) which explored experimentally the evolution of the EEPF with pressure in a capacitively coupled oxygen discharge in the pressure range 3 – 100 mTorr
- They find that the EEPF became more distinctly bi-Maxwellian and the density of low energy electrons increases as the gas pressure is increased

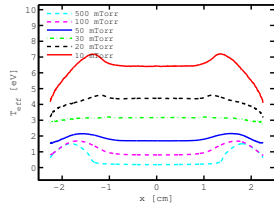
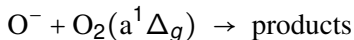


Lee et al. (2010) PRE **81** 046402

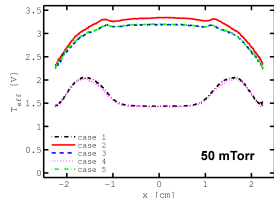


Oxygen CCP – pressure dependence

- The effective electron temperature drops as the pressure is increased
- When the metastable singlet oxygen molecule $O_2(a^1\Delta_g)$ is added to the discharge model the effective electron temperature drops, in particular in the electronegative core due to detachment by the metastable $O_2(a^1\Delta_g)$ molecule



Gudmundsson and Ventéjou (2015) JAP **118** 153302



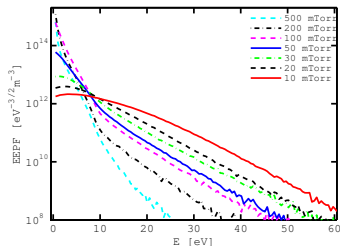
Gudmundsson and Lieberman (2015) PSST **24** 035016

Oxygen CCP – pressure dependence

- At low pressure the EEPF curves outwards and develops an inward curving shape or becomes bi-Maxwellian as the pressure is increased
- These results contradict what is commonly found for the capacitively coupled argon discharge where the EEPF evolves from being bi-Maxwellian at low pressure to being more Druyvesteyn like at high pressure

Godyak and Piejak (1990) Phys. Rev. Lett. **65** 996

Vahedi et al. (1993) Plasma Sources Sci. Technol. **2** 273



Gudmundsson and Ventéjou (2015) JAP **118** 153302

Capacitively Coupled Oxygen Discharge single frequency at 13.56 MHz

– pressure dependence –

including $\text{O}_2(\text{a}^1\Delta_g)$, $\text{O}_2(\text{b}^1\Sigma_g)$ and $\gamma_{\text{see}}(\mathcal{E})$

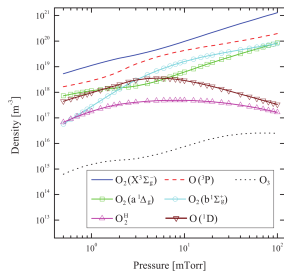
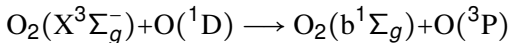


Oxygen CCP – pressure dependence

- It has been known for decades that the metastable oxygen molecule $O_2(b^1\Sigma_g)$ plays an important role in the oxygen discharge

Thompson (1961) *Proc. Royal Soc. A* 262(1311) 519

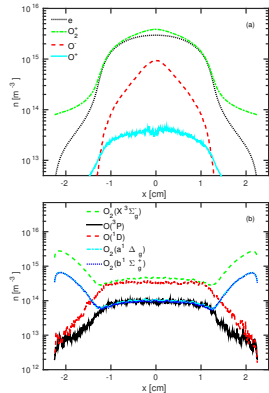
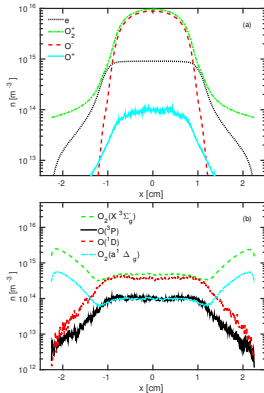
- Recent global model study indicates there is a significant density of $O_2(b^1\Sigma_g)$ in the oxygen discharge
- The $O_2(b^1\Sigma_g)$ is mainly created through



Toneli et al., *J. Phys. D*, **48** 325202 (2015)



Oxygen CCP – pressure dependence



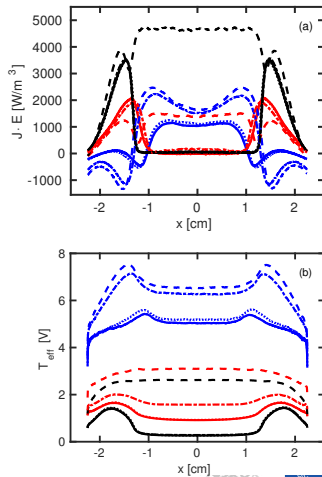
- The density profiles of charged particles and fast neutrals comparing including $O_2(a^1\Delta_g)$ (left) and $O_2(a^1\Delta_g)$ and $O_2(b^1\Sigma_g^-)$ (right) at 50 mTorr



Oxygen CCP – pressure dependence

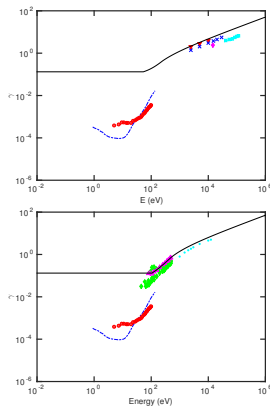
- The number of cold electrons increases and negative ion density decreases as the metastables $O_2(a^1\Delta_g)$ and $O_2(b^1\Sigma_g)$ are added to the discharge model
- The electron heating in the bulk drops to zero at the higher pressures
- The effective electron temperature profile changes significantly when detachment by singlet metastables is added to the reaction set
- **10 mTorr**, **50 mTorr** and **200 mTorr**

Gudmundsson and Hannesdottir, AIP Conf. Proc. **1811** 120001 (2017)

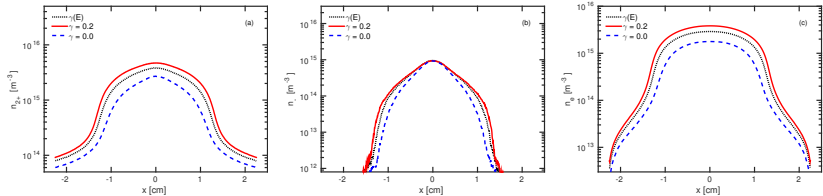


Oxygen CCP – pressure dependence

- We have compiled experimental data from the literature on secondary electron emission yields for the species O_2^+ , O^+ , O_2 and O bombarding various metals and substances
- A fit was made through the available experimental data



Oxygen CCP – pressure dependence



- The O_2^+ , O^- and electron density profiles for $\gamma_{\text{see}} = 0.0$, $\gamma_{\text{see}} = 0.2$, and energy dependent secondary electron emission yield
- The electron density increases with increased secondary electron emission yield

Oxygen CCP – pressure dependence

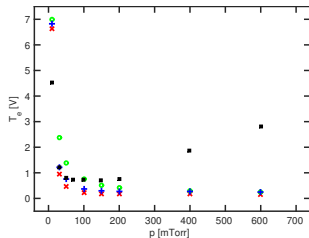
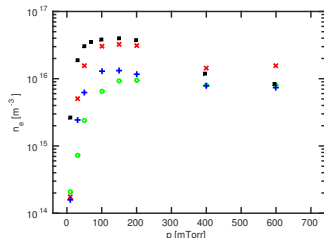
■ Comparison to experimental findings:

- $\circ \gamma_{\text{see}} = 0.0$,
4.4 % $\text{O}_2(\text{a}^1\Delta_{\text{g}})$
- $+ \gamma_{\text{see}} = 0.0$,
4.4 % $\text{O}_2(\text{a}^1\Delta_{\text{g}})$ and 4.4 % $\text{O}_2(\text{b}^1\Sigma_{\text{g}})$
- $\times \gamma_{\text{see}} = \gamma_{\text{see}}(E)$,
4.4 % $\text{O}_2(\text{a}^1\Delta_{\text{g}})$ and 4.4 % $\text{O}_2(\text{b}^1\Sigma_{\text{g}})$

■ ■ Experimental findings by Kechkar

(S. Kechkar, Ph.D. Thesis, Dublin City University, January 2015)

Hannesdottir and Gudmundsson (2016) PSST **25** 055002

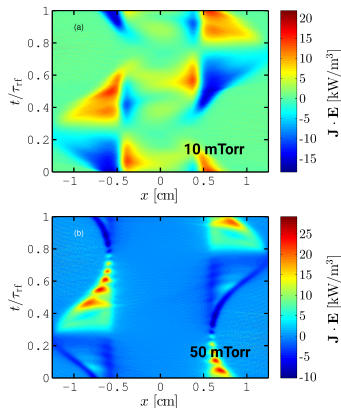


Oxygen CCP – pressure dependence

- The spatio-temporal electron heating $\mathbf{J}_e \cdot \mathbf{E}$ at 10 and 50 mTorr
- At 10 mTorr there is a significant electron heating within the electronegative core
- At 50 mTorr the electron heating occurs almost solely in the sheath region

Hannesdottir and Gudmundsson (2016) PSST, **25** 055002

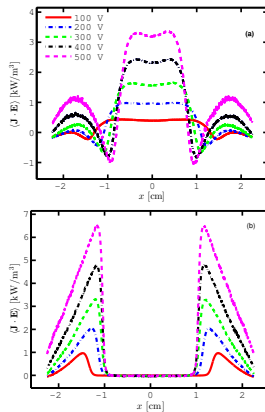
Gudmundsson and Ventéjou (2015) JAP **118** 153302



Gudmundsson and Snorrason (2017) JAP **122** 193302

Oxygen CCP – pressure dependence

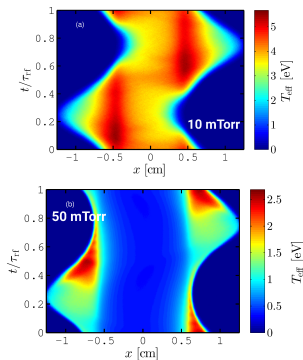
- The time averaged electron heating $\langle \mathbf{J}_e \cdot \mathbf{E} \rangle$ at 10 and 50 mTorr
- At 10 mTorr there is significant electron heating within the electronegative core
- At 50 mTorr, the heating rate in the electronegative core is roughly zero, and electron heating is almost entirely located in the sheath regions



Gudmundsson and Snorrason (2017) JAP **122** 193302

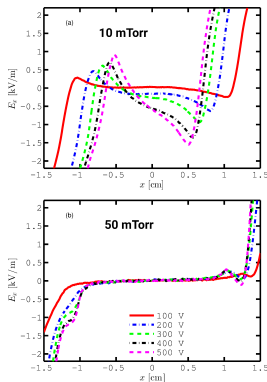
Oxygen CCP – pressure dependence

- At 10 mTorr the effective electron temperature is high within the plasma bulk (the electronegative core) throughout the rf period and peaks within the plasma bulk during the sheath collapse phase
- At 50 mTorr a peak in the effective electron temperature within the plasma bulk in the sheath expansion phase and is low within the plasma bulk throughout the rf period



Oxygen CCP – pressure dependence

- The axial electric field at $t/\tau_{rf} = 0.5$ for both 10 and 50 mTorr
- At 10 mTorr there is a significant electric field strength within the electronegative core
- This strong electric field within the plasma bulk (the electronegative core) indicates a drift-ambipolar (DA) heating mode
- This electric field is a combination of a drift field and an ambipolar field
- At 50 mTorr the electric field is zero within the electronegative core



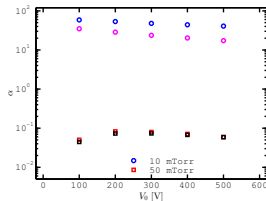
Schulze et al. (2011) Phys. Rev. Lett. **107** 275001

Gudmundsson and Snorrason (2017) JAP **122** 193302



Oxygen CCP – pressure dependence

- The electronegativity is significantly higher when operating at 10 mTorr than when operating at 50 mTorr
- At 10 mTorr, the discharge is operated in a combined drift-ambipolar (DA) and α -mode
- At 50 mTorr, the discharge is in a pure α -mode and sheath heating dominates
- The transition from the combined DA- α -mode to the pure α -mode coincides with a significant decrease in the electronegativity



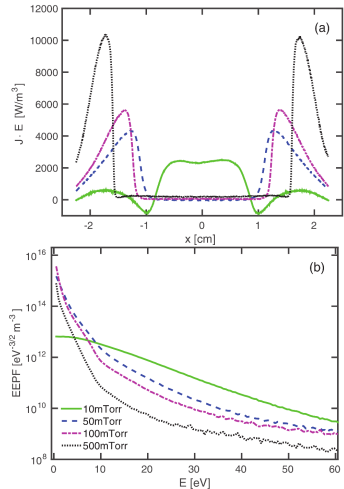
Gudmundsson and Snorrason (2017) JAP **122** 193302

Oxygen CCP – pressure dependence

- At low pressure the EEPF curves outwards, the population of low energy electrons is relatively low
- As the pressure is increased the number of low energy electrons increases and the number of higher energy electrons (> 10 eV) decreases
- Thus the EEPF develops a bi-Maxwellian shape as the pressure is increased

Hannesdottir and Gudmundsson (2016) PSST, **25** 055002

Gudmundsson and Ventéjou (2015) JAP **118** 153302



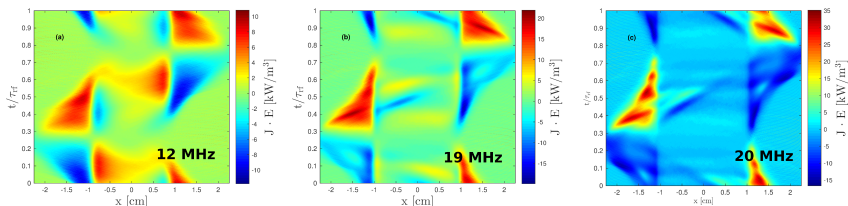
Capacitively Coupled Oxygen Discharge single frequency at 10 mTorr

– driving frequency dependence –

including $\text{O}_2(\text{a}^1\Delta_g)$, $\text{O}_2(\text{b}^1\Sigma_g)$ and $\gamma_{\text{see}}(\mathcal{E})$



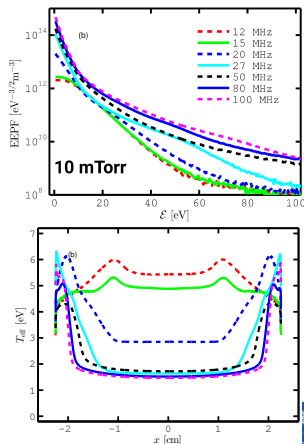
Oxygen CCP – frequency dependence



- At 12 MHz significant heating is observed in the plasma bulk but also in the sheath region
- At 19 MHz the heating and cooling in the sheath regions has increased, however there is contribution to the electron heating in the bulk region (note the change in scale)
- At 20 MHz there is almost no electron heating in the plasma bulk

Oxygen CCP – frequency dependence

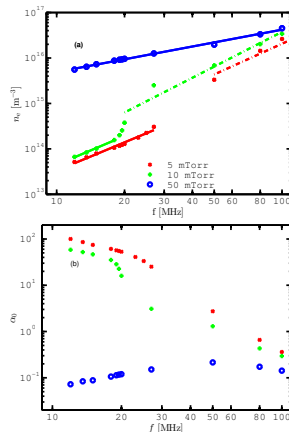
- At low driving frequency the EEPF is convex, the population of low energy electrons is relatively low
- The EEPF remains convex for driving frequency up to 15 MHz and has transitioned to concave or bi-Maxwellian shape at 20 MHz
- Increasing the driving frequency enhances the high energy tail as the number of high energy electrons increases



Gudmundsson et al. (2018) PSST 27 025009

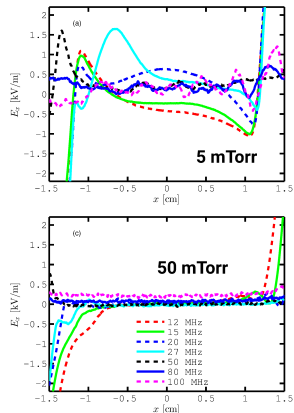
Oxygen CCP – frequency dependence

- At 10 mTorr there is a jump in the center electron density between 20 and 27 MHz
- At 10 mTorr $n_e \propto f^{2.11}$ at low frequency, below 18 MHz, and $n_e \propto f^{2.00}$ at higher frequencies, 27.12 MHz and above
- At 50 mTorr $n_e \propto f^{1.16}$ over the entire frequency range explored and no transition is observed
- We see that at 5 and 10 mTorr the electronegativity decreases with increasing driving frequency



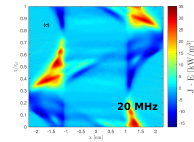
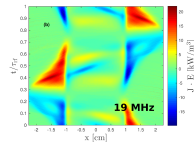
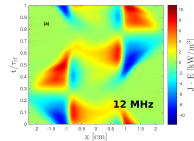
Oxygen CCP – frequency dependence

- The electric field profile at $t/\tau_{\text{rf}} = 0.5$ for discharges operated at 5 and 50 mTorr
- We see a significant electric field strength within the electronegative core at low driving frequency and low pressure
- The strong electric field within the plasma bulk (the electronegative core), at low pressure and low driving frequency, indicates a drift-ambipolar (DA) heating mode



Oxygen CCP – frequency dependence

- At a low driving frequency and low pressure (5 and 10 mTorr), a combination of stochastic (α -mode) and drift ambipolar (DA) heating in the bulk plasma (the electronegative core) is observed
- The DA-mode dominates the time averaged electron heating
- As the driving frequency is increased, the heating mode transitions into a pure α -mode
- At low pressure (5 and 10 mTorr), this transition coincides with a sharp decrease in electronegativity



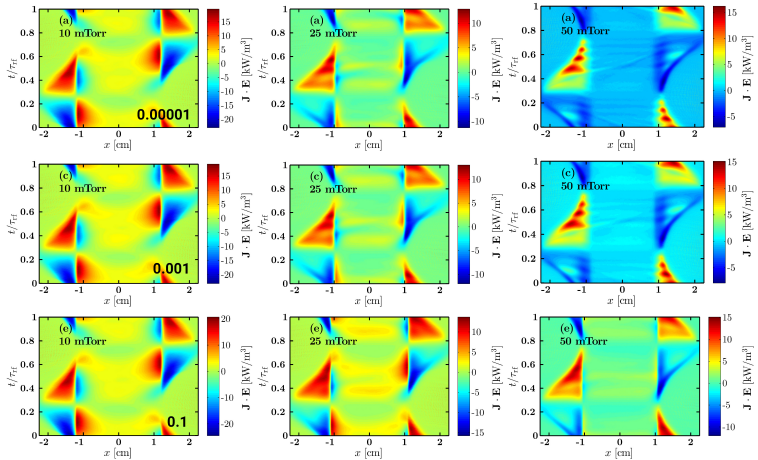
Capacitively Coupled Oxygen Discharge

– surface quenching of $\text{O}_2(\text{a}^1\Delta_g)$ –

including $\text{O}_2(\text{a}^1\Delta_g)$, $\text{O}_2(\text{b}^1\Sigma_g)$ and $\gamma_{\text{see}}(\mathcal{E})$

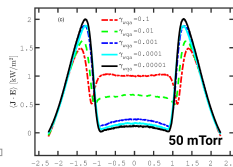
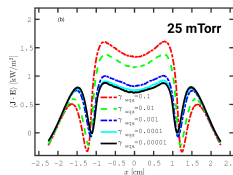
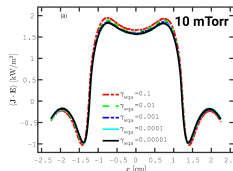


Oxygen CCP – surface quenching of $O_2(a^1\Delta_g)$



Oxygen CCP – surface quenching of $O_2(a^1\Delta_g)$

- At 10 mTorr almost all the electron heating occurs in the plasma bulk (the electronegative core) and the electron heating profile is independent of the surface quenching coefficient
- At 50 mTorr only for the highest surface quenching coefficients 0.1 and 0.01 there is some electron heating observed in the bulk region
- Typical value is 0.007 for iron (Sharpless and Slinger, 1989)



Proto and Gudmundsson (2018) PSST 27 074002

Capacitively Coupled Oxygen Discharge

– the effect of $\gamma_{\text{see}}(\mathcal{E})$ –

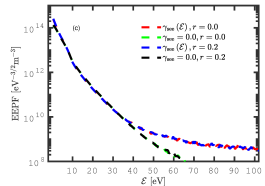
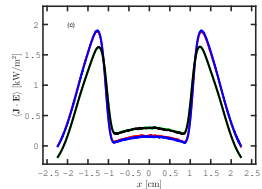
including $\text{O}_2(\text{a}^1\Delta_g)$, $\text{O}_2(\text{b}^1\Sigma_g)$ and $\gamma_{\text{see}}(\mathcal{E})$



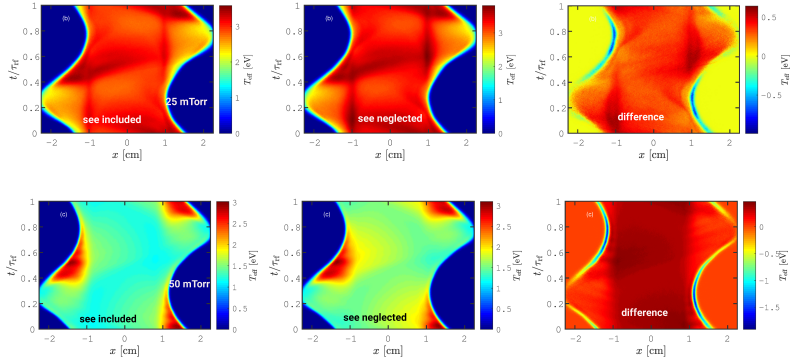
Oxygen CCP – the effect of $\gamma_{\text{see}}(\mathcal{E})$

- Adding secondary electron emission yield
 - increases the electron density
 - increases the electron heating rate in the sheath region
 - the sheath region becomes narrower
 - a high energy tail appears in the EEPF

Hannesdottir and Gudmundsson, PSST, **25** 055002 (2016)



Oxygen CCP – the effect of $\gamma_{\text{see}}(\mathcal{E})$

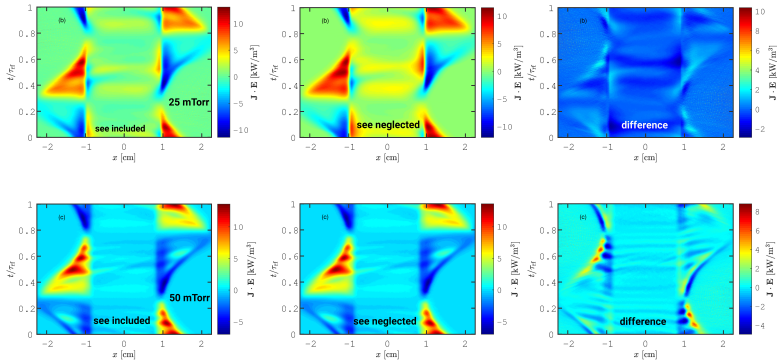


Proto and Gudmundsson (2018) Atoms (submitted September 2018)

- Including secondary electron emission increases the electron energy



Oxygen CCP – the effect of $\gamma_{\text{see}}(\mathcal{E})$



Proto and Gudmundsson (2018) Atoms (submitted September 2018)

- Including secondary electron emission decreases the electron power absorption



Summary



Summary

- We demonstrated particle-in-cell/Monte Carlo collision simulation of a capacitively coupled discharge
- Including the detachment processes by the singlet metastable states has a strong influence on the effective electron temperature and electronegativity in the oxygen discharge
- At low pressure the discharge is operated in a combined drift-ambipolar (DA) and α -mode, and at higher pressure it is operated in the pure α -mode



Summary

- We demonstrated particle-in-cell/Monte Carlo collision simulation of a capacitively coupled discharge
- In an oxygen discharge at low pressure the EEPF curves outward and develops a bi-Maxwellian shape as the pressure is increased
- These results contradict what is commonly found for the capacitively coupled argon discharge where the EEPF evolves from being bi-Maxwellian at low pressure to being more Druyvesteyn like at high pressure
 - the reason is the high electronegativity at low pressure in an oxygen discharge – DA heating



C. Overall Summary



Overall Summary

- A global (volume averaged) model can be used to understand the plasma chemistry
 - Which particles are important
 - Which reactions are important
 - How do the plasma parameters scale with the control parameters – power, pressure, discharge dimensions
- Particle-in-cell/Monte Carlo collision simulations can be used to explore the plasma kinetics
 - To determine the electron heating mechanism
 - To find the electron energy distribution function
 - To find the ion energy distribution (IED) and the ion angular distribution (IAD)



Overall Summary

- There is clearly a need for basic experimental work on capacitively coupled oxygen discharges
 - Langmuir probe measurements, EEDF, T_{eff} , n_e versus pressure and applied voltage
 - Electronegativity for various pressures and applied voltage
- The rate coefficient for detachment by $\text{O}_2(\text{b}^1\Sigma_g)$ has to be reevaluated
- What is the role of electron impact dissociative attachment from vibrationally excited molecular states ?
- What is the role of the metastable Herzberg states $\text{O}_2(\text{A}^3\Sigma_u^+, \text{A}'^3\Delta_u, \text{c}^1\Sigma_u^-)$?
- Measurements of the wall quenching coefficient of $\text{O}_2(\text{b}^1\Sigma_g)$ are needed



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The slides can be downloaded at

<http://langmuir.raunvis.hi.is/~tumi/ranns.html>

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